

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent No. 7183220B1
Patent Issue Date February 27, 2007
Application Serial No. 09677478
Filing Date October 2, 2000
Assignee Micron Technology, Inc.
Inventorship Blalock, Guy T.
Attorney's Docket No. MI22-1544
Title: Plasma Etching Methods

REQUEST FOR CERTIFICATE OF CORRECTION OF PATENT
FOR APPLICANT MISTAKES AND PTO MISTAKES (37 C.F.R. 1.322(a) and
1.323)

To: Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450
ATTN: Decision and Certificate of Correction
 Branch of the Patent Issue Division

From: D. Brent Kenady (Tel. 509-624-4276; Fax 509-838-3424)
 Wells St. John P.S.
 601 W. First Avenue, Suite 1300
 Spokane, WA 99201-3828

Sir/Madam:

It is hereby requested that a Certificate of Correction be issued with respect to Patent No. 7183220B1, granted February 27, 2007, in accordance with the Certificate of Correction Form PTO-1050 attached hereto.

It is noted that errors appear in this patent of a typographical nature of character, as more fully described below. The error(s) occurred in good faith. Correction thereof does not involve such changes in the patent as would constitute new matter or would require re-examination.

The other error(s) listed on the Certificate of Correction form were apparently incurred through the fault of the PTO as will be disclosed by the records of files in the Office.

Enclosed is a check in the amount of \$100.00, as required by 37 CFR 1.20(a).

Respectfully submitted,

Dated: 8-4-08

By:


D. Brent Kenady
Reg. No. 40045

UNITED STATES PATENT AND TRADEMARK OFFICE
CERTIFICATE OF CORRECTION

Page 1 of 2

PATENT NO. : 7183220B1

APPLICATION NO.: 09677478

DATED : February 27, 2007

INVENTOR(S) : Blalock, Guy T.; Becker, David S.; Donohoe, Kevin G.

It is certified that an error or errors appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Page 2, first column, U.S. PATENT DOCUMENTS, please insert- -
5,814,888 9/1988 Nishioka et al. - - before "5,817,578"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
5,872,061 2/1999 Lee et al. - - before "5,873,948"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
5,933,759 8/1999 Nguyen et al. - - before "5,935,340"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
5,968,844 10/1999 Keller- - before "6,093,655"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
6,010,967 1/2000 Donohoe et al. - - before "6,093,655"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
6,127,278 10/2000 Wang et al. - - before "6,136,211"

Page 2, second column, U.S. PATENT DOCUMENTS, please insert- -
6,258,728 B1 7/2001 Donohoe et al. - - before "6,434,327"

Mailing Address of Sender:

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Page 2, second column, U.S. PATENT DOCUMENTS, please insert -

6,478,978 11/2002 Allen

6,479,393 11/2002 Allen- - before "6,533,953"

Column 1, BACKGROUND OF THE INVENTION, line 57

Please replace "the photoresist from the"

With- - the photoresist from- -

Column 1, BACKGROUND OF THE INVENTION, line 60

Please replace "there is the contact."

With- - there is an approximate 0.025 micron or greater loss in the lateral direction of the contact. - -

Column 2, BACKGROUND OF THE INVENTION, line 7

Please replace "the invention only be limited by the"

With- - the invention only being limited by the- -

Column 3, line 66

Please replace "etching conducted"

With- - etching is conducted- -

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